

Figure 1

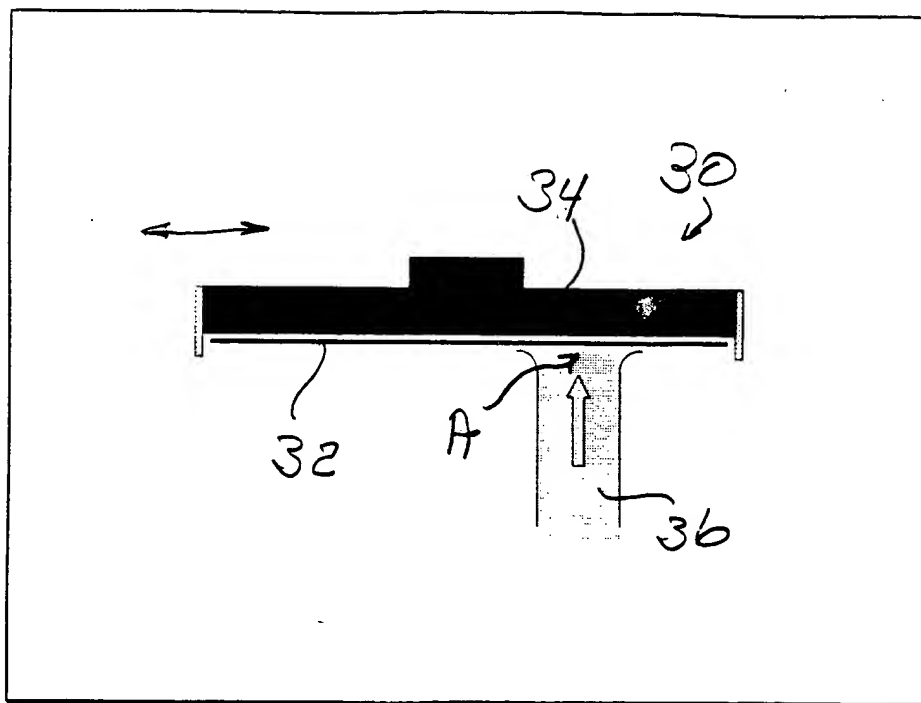


Figure 2

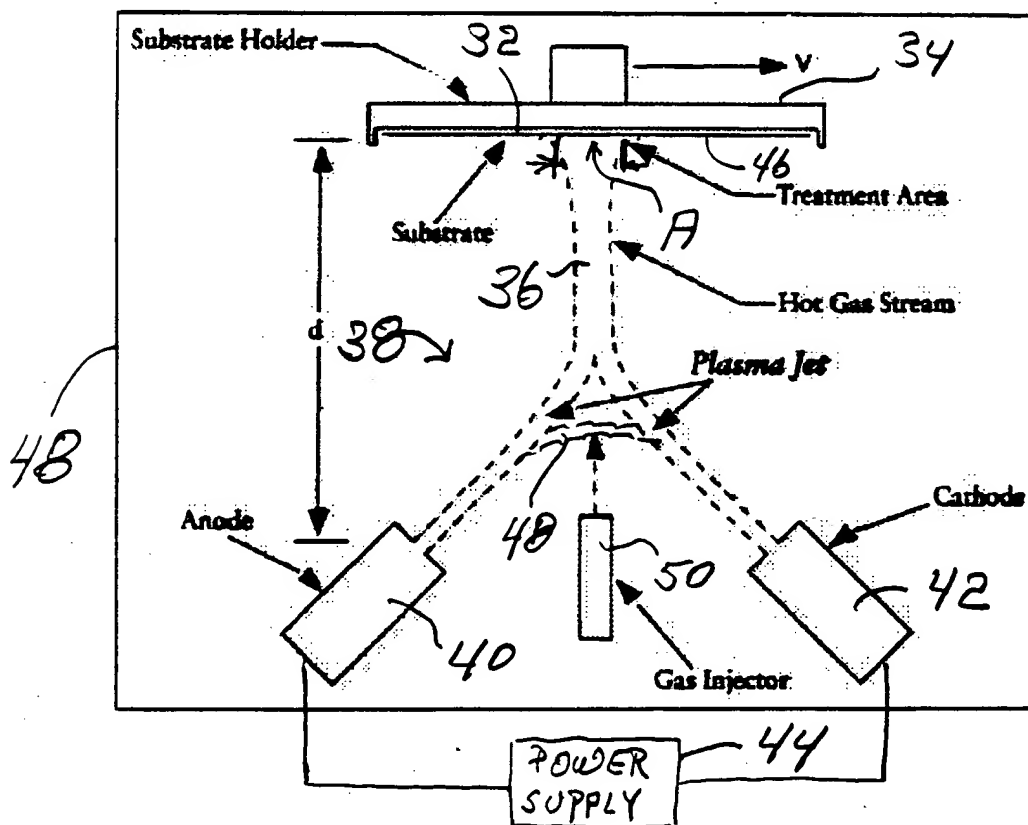


Figure 3 A

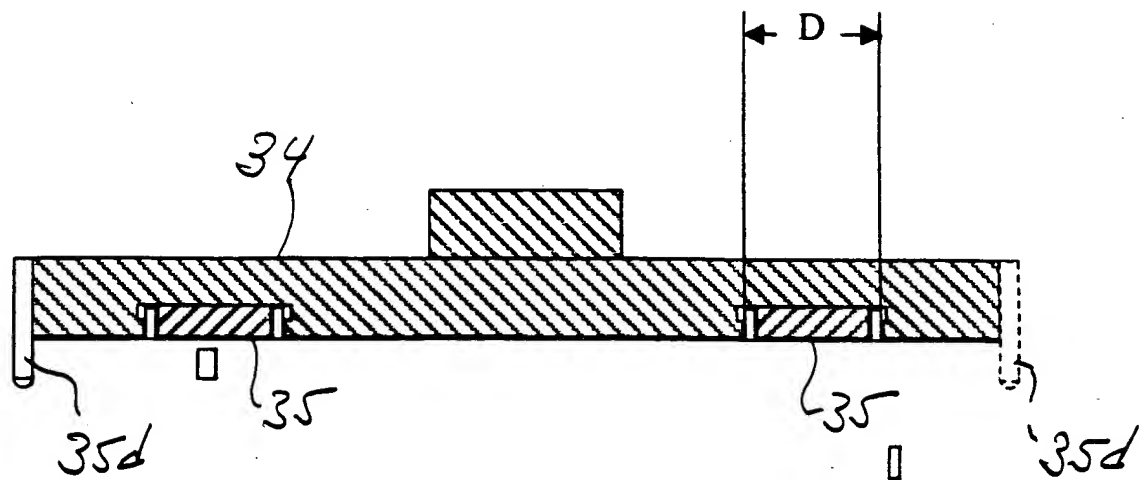


Fig 3B

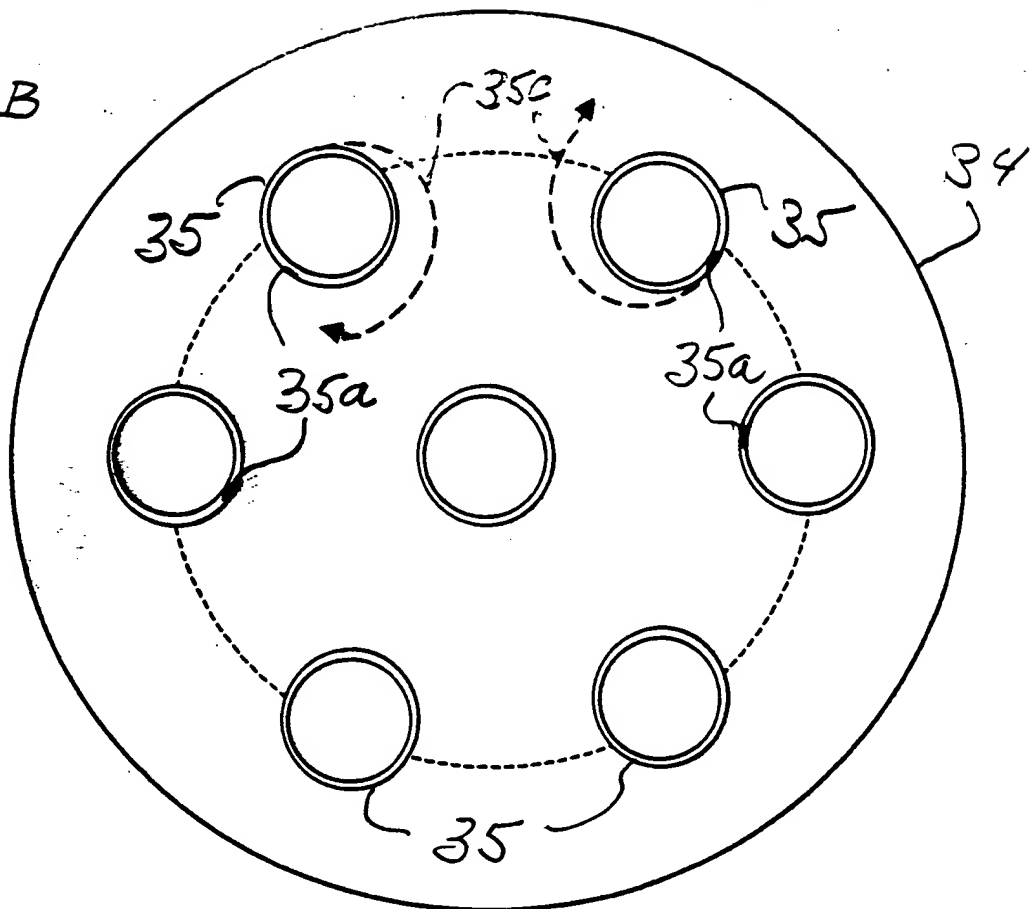
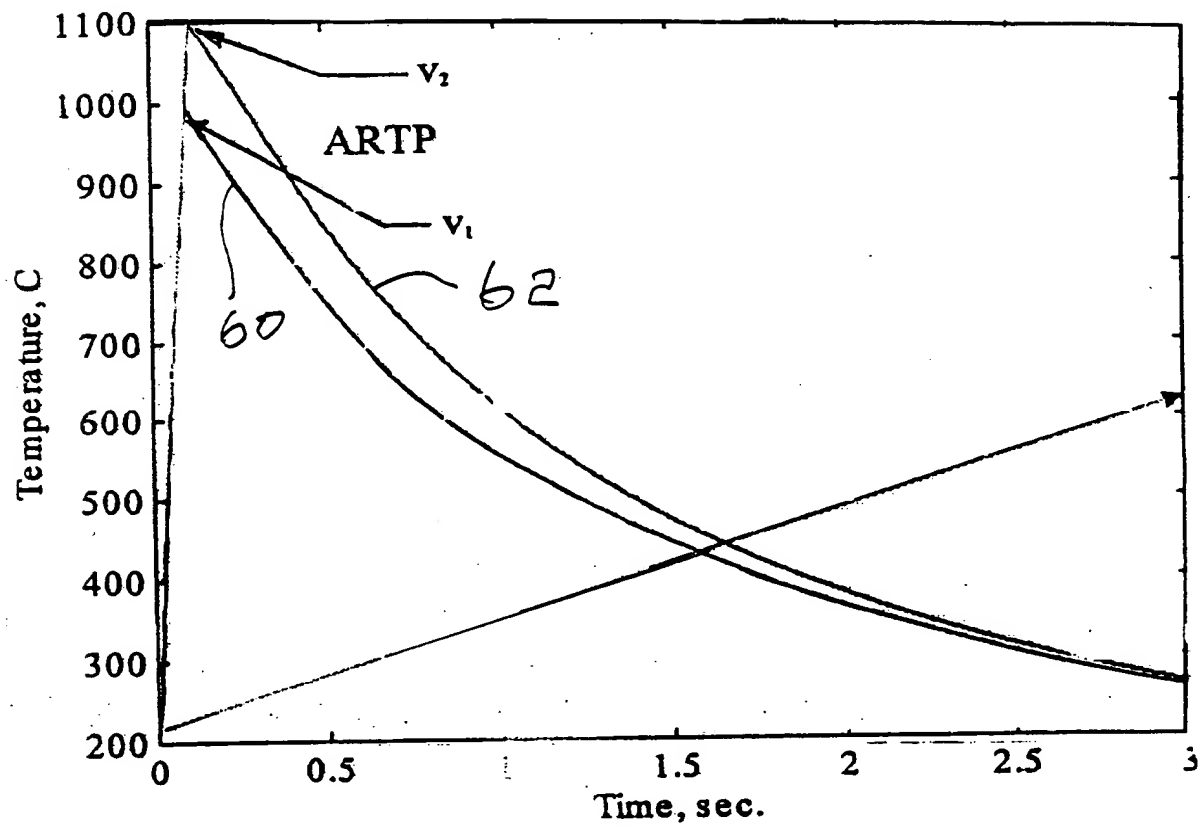


Figure 4



000207 24 FEB 60

Figure 5

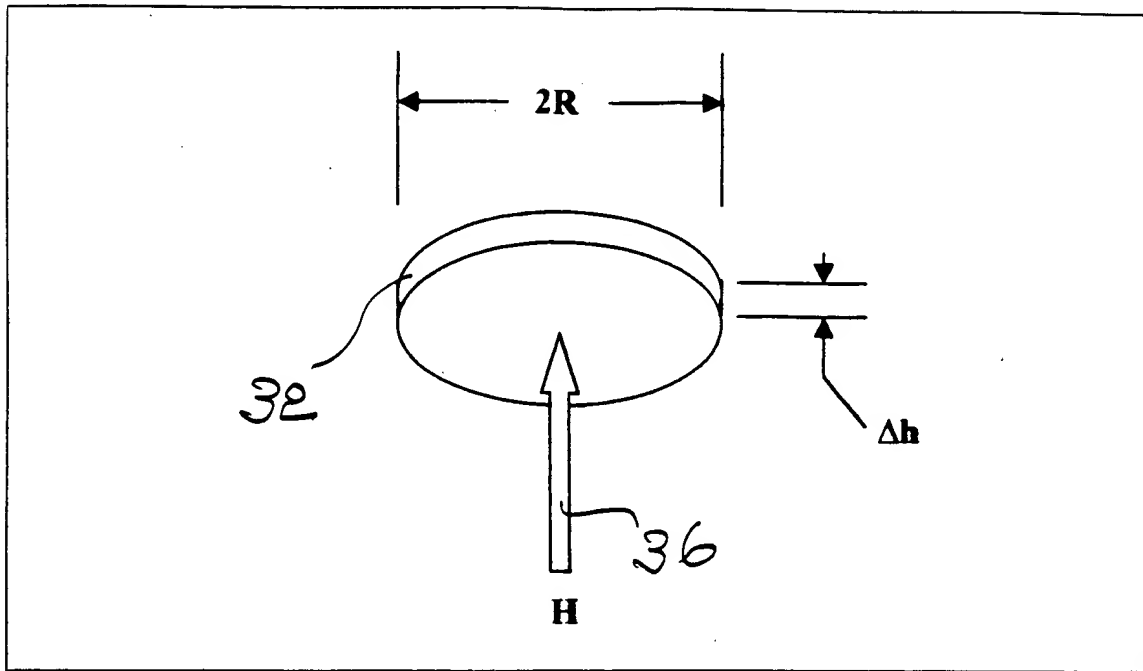


Figure 6

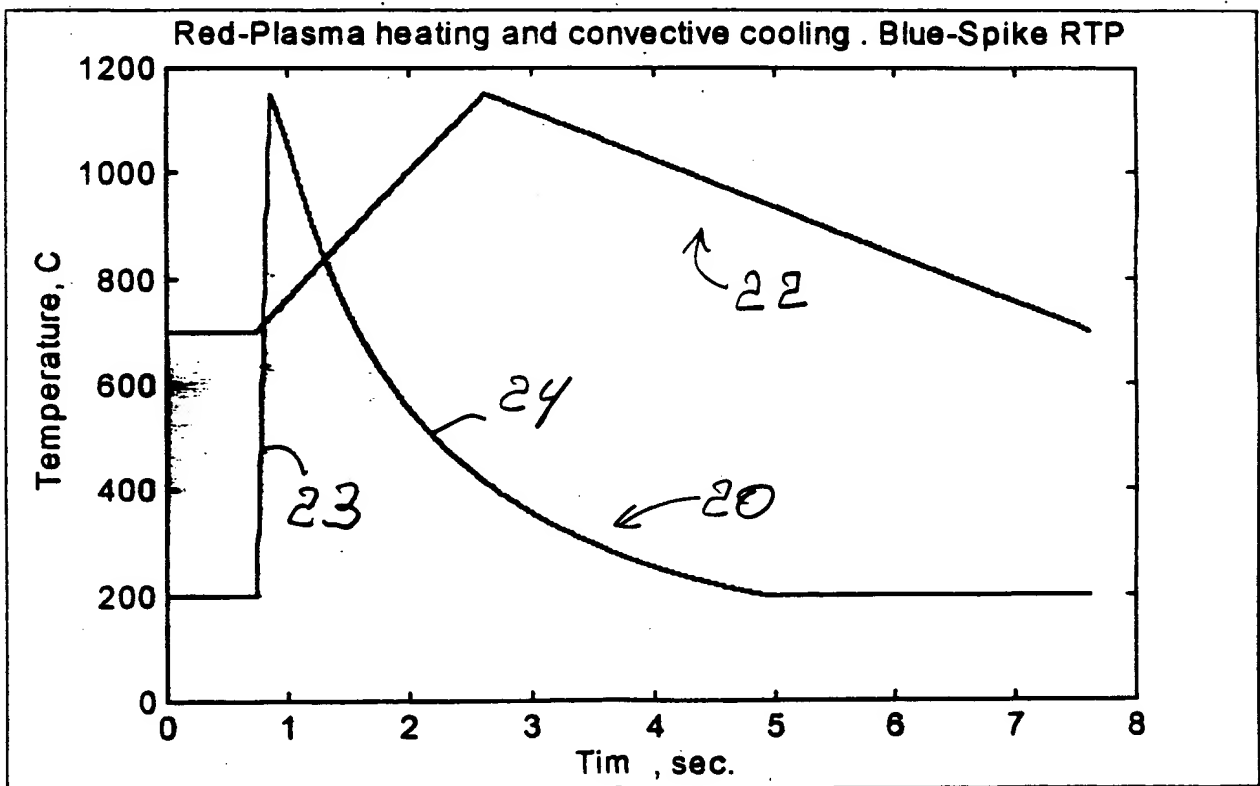


Figure 7

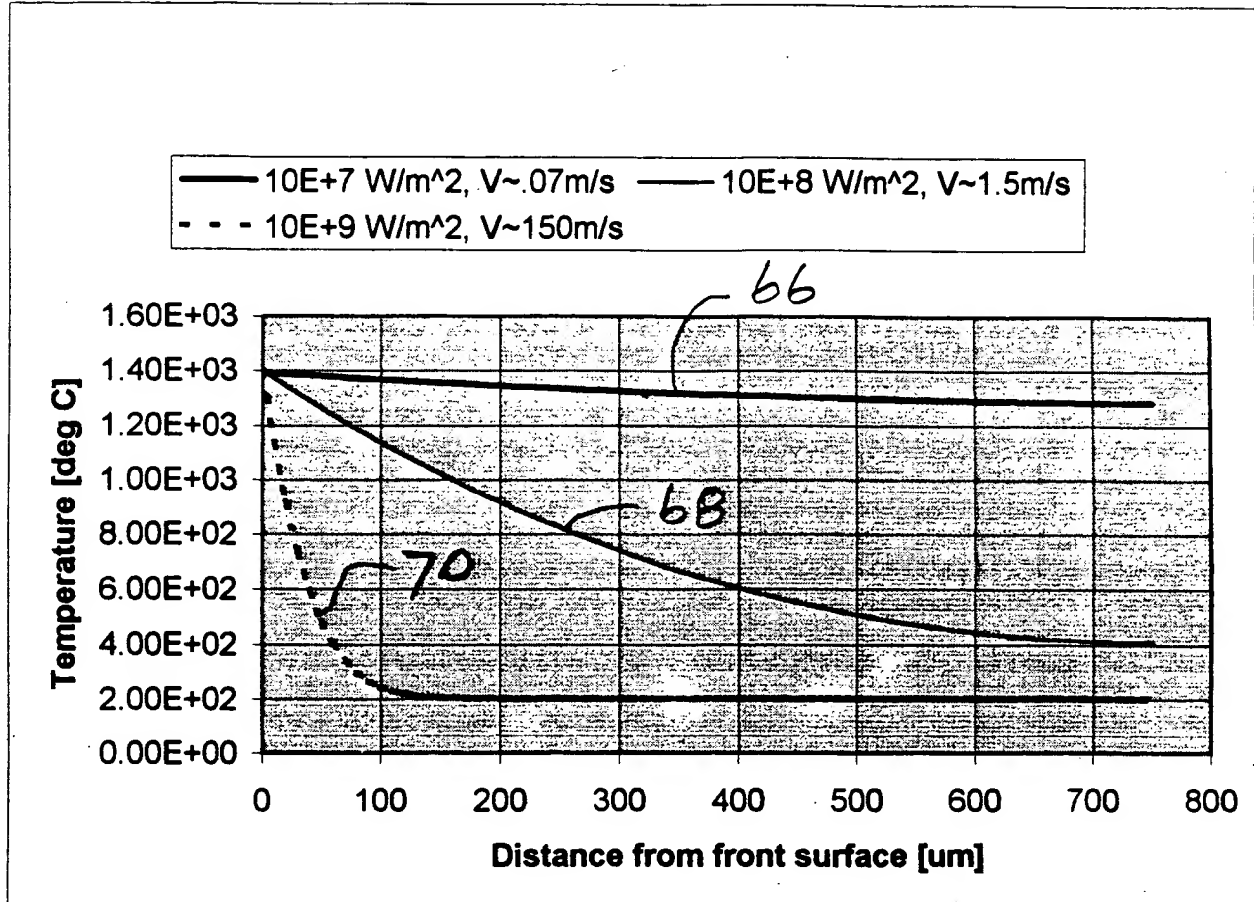


Figure 8

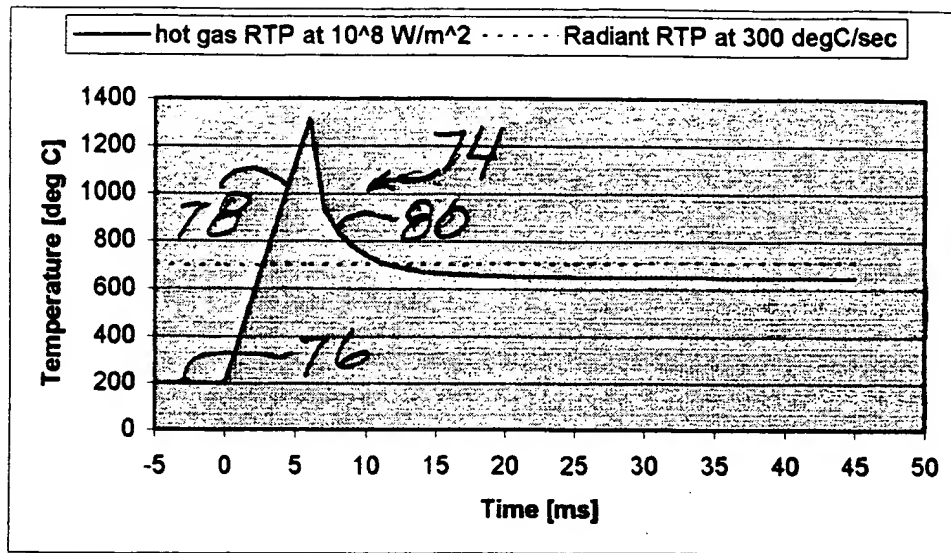


Figure 9

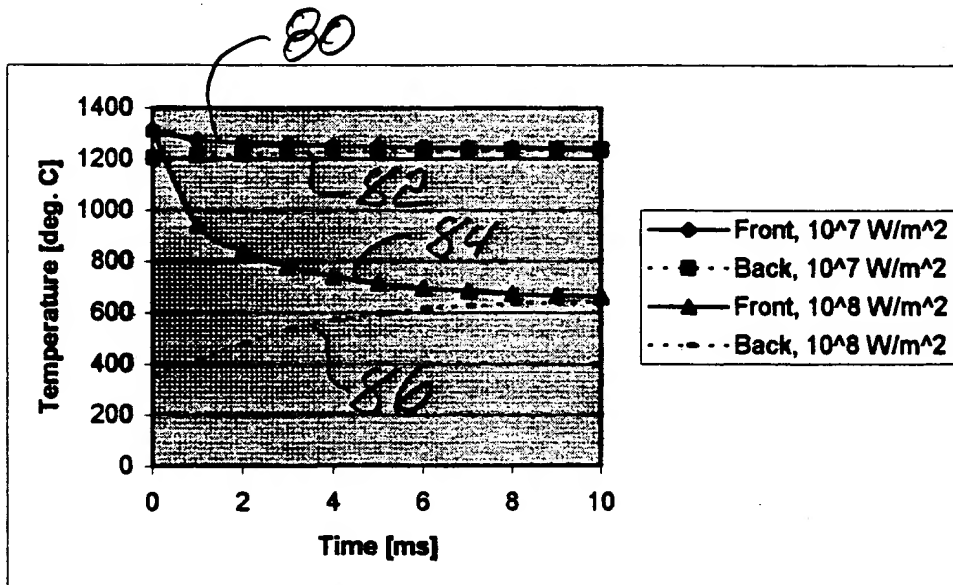


Figure 10

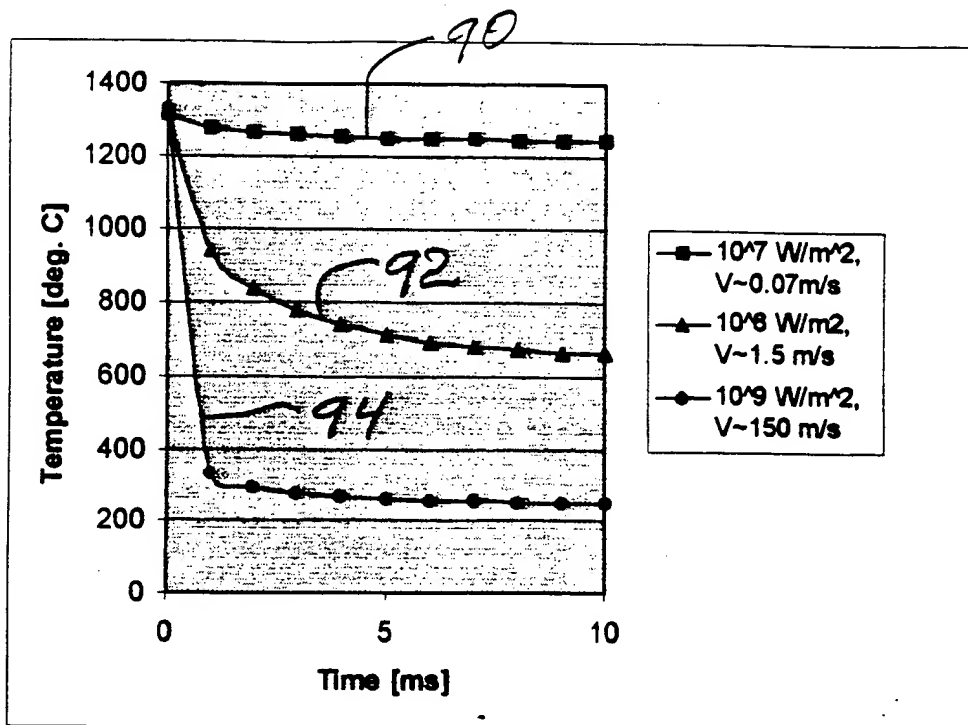


Figure 11

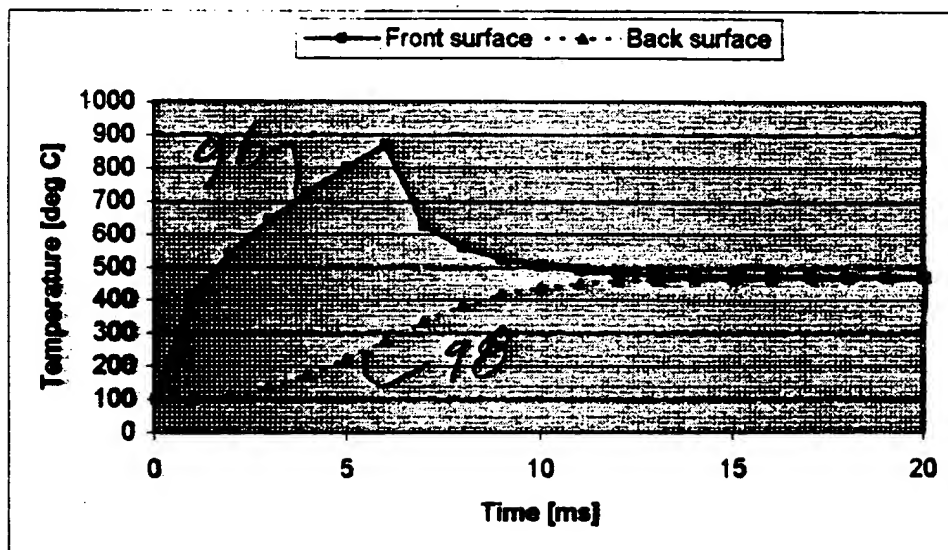
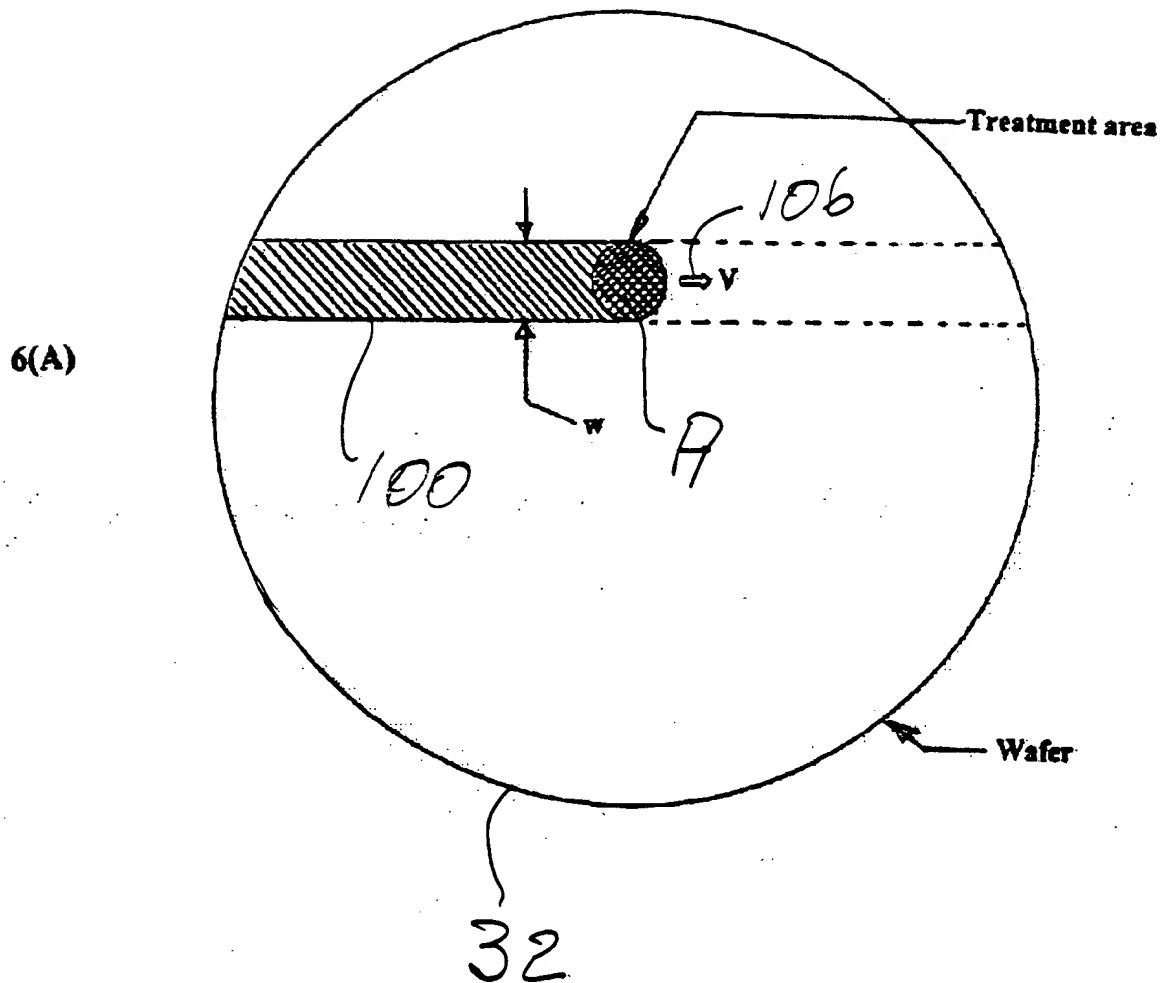
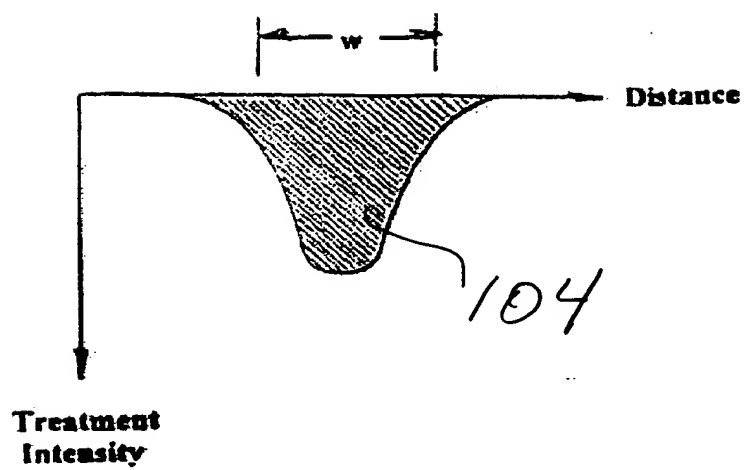


Figure 12



6(B)



104

[illegible]

Figure 14

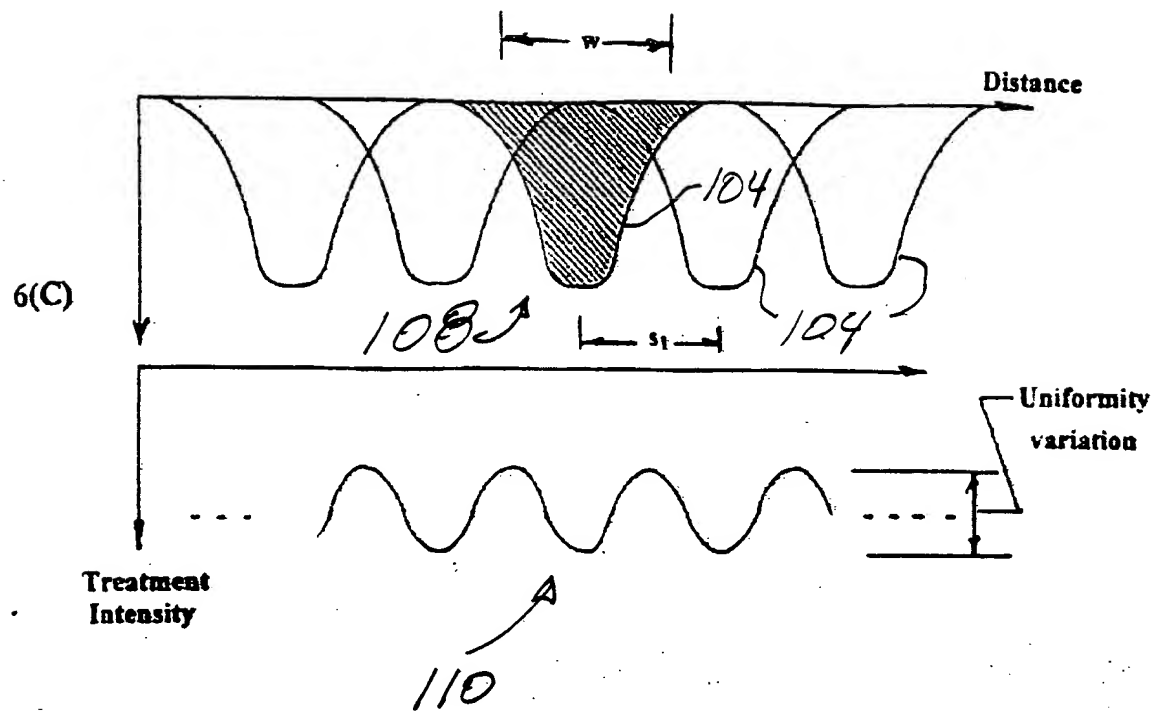


Figure 15

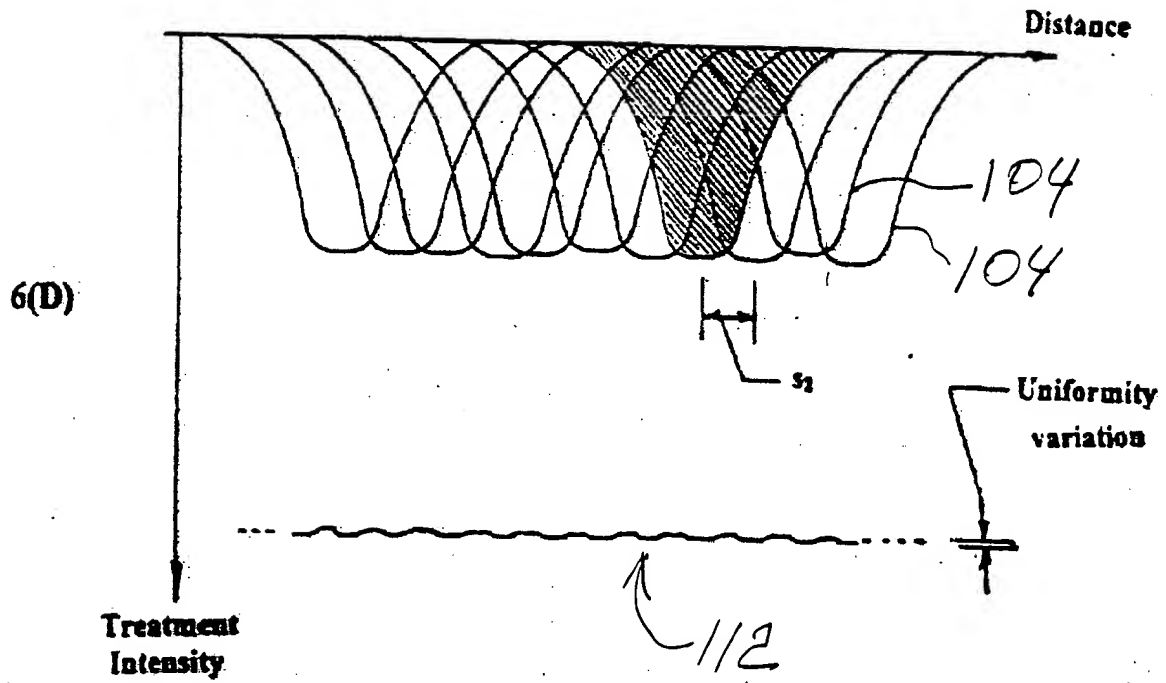


Figure 17

(A)

34

128

Wafer

46 A

Stream of hot reactant gas

36

Treatment area

